

***Supporting Information for***  
**Elemental Quantitative Imaging Analysis of Bi<sub>4</sub>Si<sub>3</sub>O<sub>12</sub> Crystals Defects by  
LA-ICP-MS**

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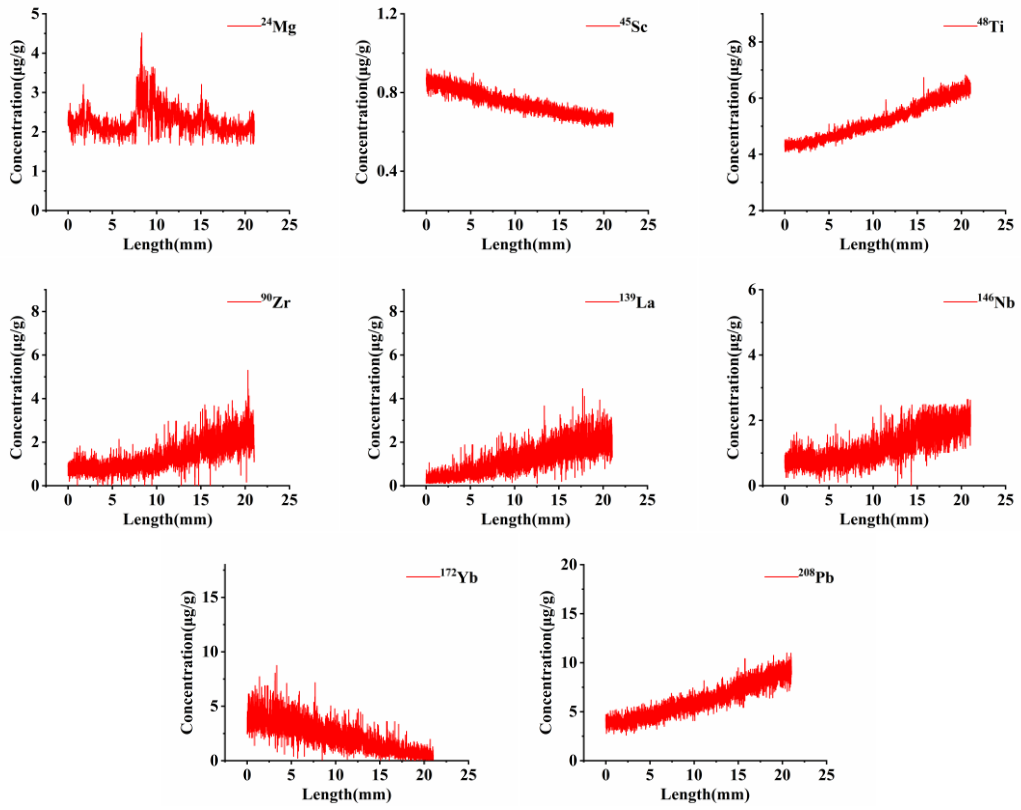
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**Fig. S1.** Distribution of impurity elements in the axial direction of the  $\text{Bi}_4\text{Si}_3\text{O}_{12}$  crystal.